

INFORMATION DISCLOSURE STATEMENT

Applicant : Hirayama et al.

App. No : 10/590,046

Filed : June 15, 2007

For : BASE MATERIAL FOR PATTERN-
FORMING MATERIAL, POSITIVE
RESIST COMPOSITION AND
METHOD OF RESIST PATTERN
FORMATION

Examiner : Johnson, Connie P.

Art Unit : 1795

**CERTIFICATE OF EFS WEB
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I hereby certify that this correspondence, and any other attachment noted on the automated Acknowledgement Receipt, is being transmitted from within the Pacific Time zone to the Commissioner for Patents via the EFS Web server on:

March 15, 2011
(Date)

/Neil S. Bartfeld/
Neil S. Bartfeld, Ph.D., Reg. No. 39,901

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

Enclosed for filing in the above-identified application is a PTO/SB/08 Equivalent listing 1 (one) reference to be considered by the Examiner. Please place this document in the application file.

No fees are believed to be due. However, the Commissioner is hereby authorized to charge any additional fees which may be required to Account No. 11-1410.

Respectfully submitted,

KNOBBE, MARTENS, OLSON & BEAR, LLP

Dated: March 15, 2011

By: /Neil S. Bartfeld/
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